## Kang-Yi Lin

List of Publications by Year in descending order

Source: https://exaly.com/author-pdf/201742/publications.pdf

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10	221	7	10
papers	citations	h-index	g-index
10	10	10	417 citing authors
all docs	docs citations	times ranked	

#	Article	IF	CITATIONS
1	Effect of Surface Potential on NIH3T3 Cell Adhesion and Proliferation. Journal of Physical Chemistry C, 2014, 118, 14464-14470.	1.5	57
2	Effect of Surface Potential on Extracellular Matrix Protein Adsorption. Langmuir, 2014, 30, 10328-10335.	1.6	45
3	Achieving ultrahigh etching selectivity of SiO2 over Si3N4 and Si in atomic layer etching by exploiting chemistry of complex hydrofluorocarbon precursors. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2018, 36, .	0.9	40
4	Effect of Surface Potential on the Adhesion Behavior of NIH3T3 Cells Revealed by Quartz Crystal Microbalance with Dissipation Monitoring (QCM-D). Journal of Physical Chemistry C, 2017, 121, 533-541.	1.5	32
5	Selective atomic layer etching of HfO2 over silicon by precursor and substrate-dependent selective deposition. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2020, 38, .	0.9	16
6	Improvement of the gas cluster ion beam-(GCIB)-based molecular secondary ion mass spectroscopy (SIMS) depth profile with O <sub>2</sub> <sup>+</sup> cosputtering. Analyst, The, 2016, 141, 2523-2533.	1.7	9
7	Assessment of the Effects of Surface Potential on the Kinetics of HEK293T Cell Adhesion Behavior Using a Quartz Crystal Microbalance with Dissipation Monitoring. Journal of Physical Chemistry C, 2018, 122, 694-704.	1.5	9
8	Enhancing the Sensitivity of Molecular Secondary Ion Mass Spectrometry with C <sub>60</sub> <sup>+</sup> -O <sub>2</sub> <sup>+</sup> Cosputtering. Analytical Chemistry, 2013, 85, 3781-3788.	3.2	7
9	Significance of plasma-photoresist interactions for atomic layer etching processes with extreme ultraviolet photoresist. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2020, 38, .	0.9	4
10	Ag Electromigration Against Electron Flow in Sn5Ag/Cu Solder Bump. Electrochemical and Solid-State Letters, 2009, 12, H445.	2.2	2